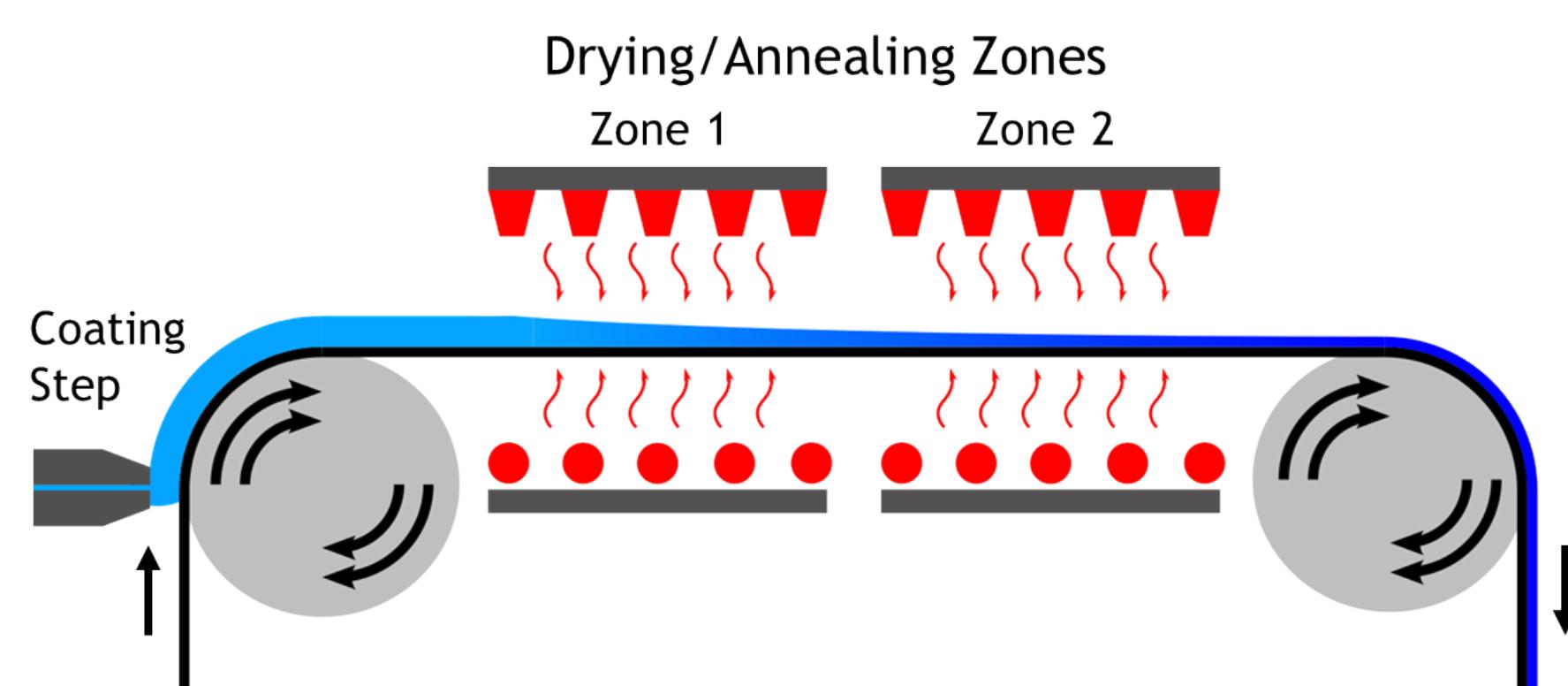


Benchtop Experimental and Computational Design Tools for Continuous Drying Processes

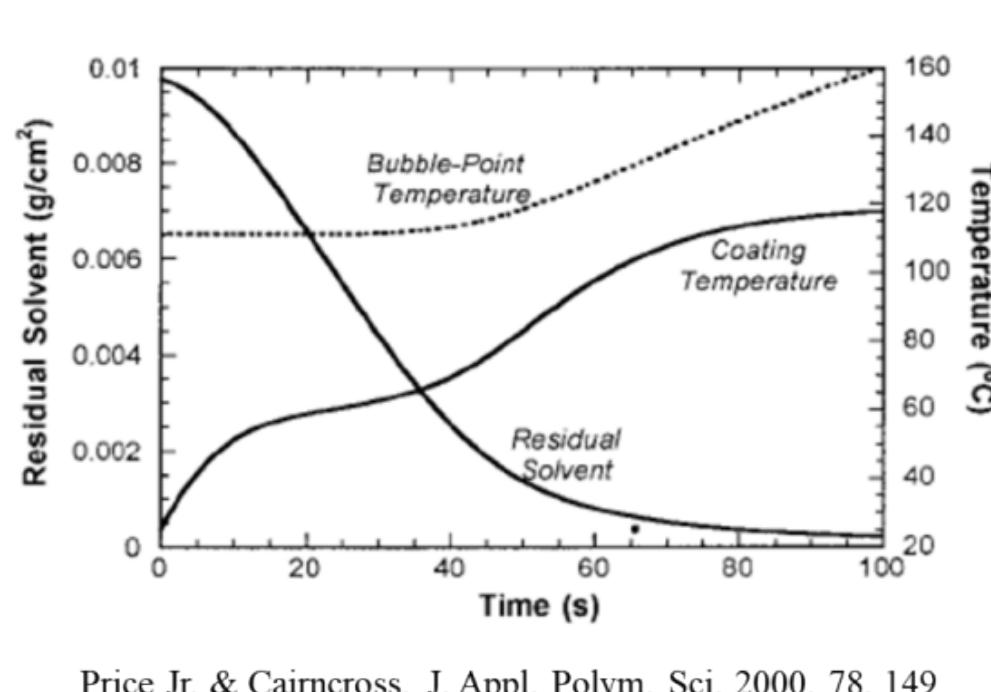
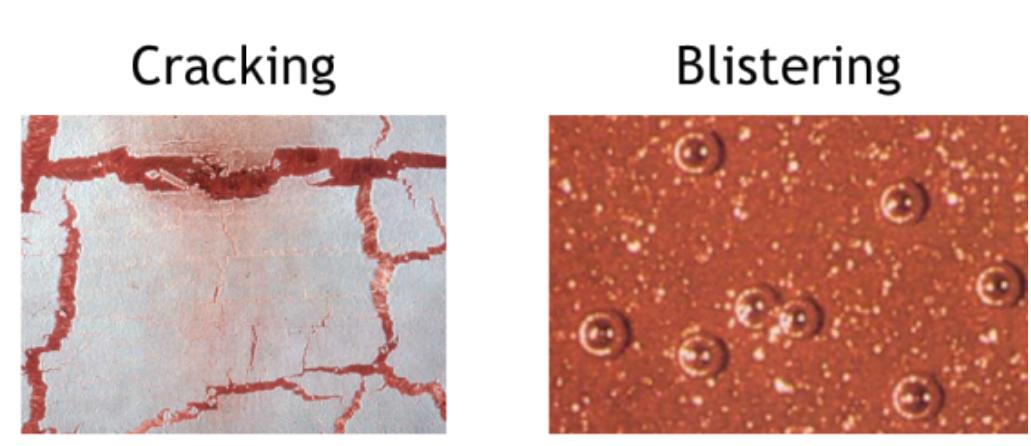
Chance Parrish¹, Nelson Bell¹, Kristianto Tjiptowidjojo², Marvin Larsen², P. Randal Schunk^{1,2}

¹ Sandia National Laboratories ² University of New Mexico

Continuous Coating and Drying Processes



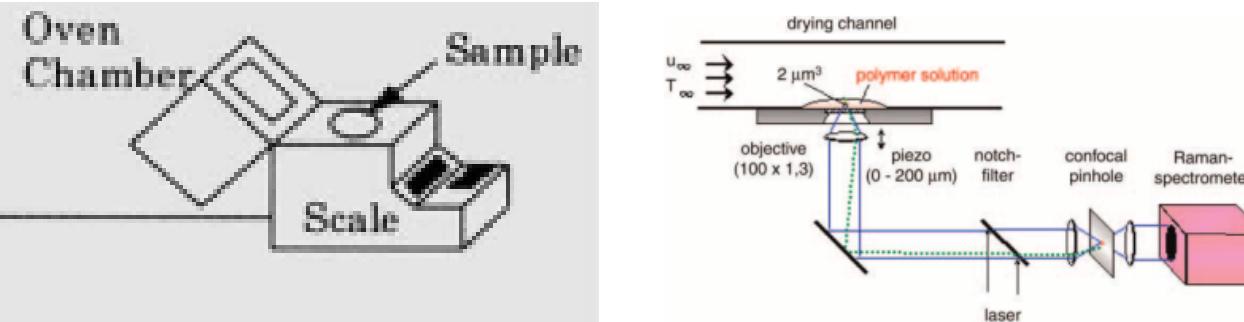
- Continuous coating and drying processes key manufacturing process
- Defects may arise for poor drying conditions, limiting process throughput
- Necessary to obtain key thermodynamic and diffusivity model parameters for drying oven design



Price Jr. & Cairncross, J. Appl. Polym. Sci. 2000, 78, 149

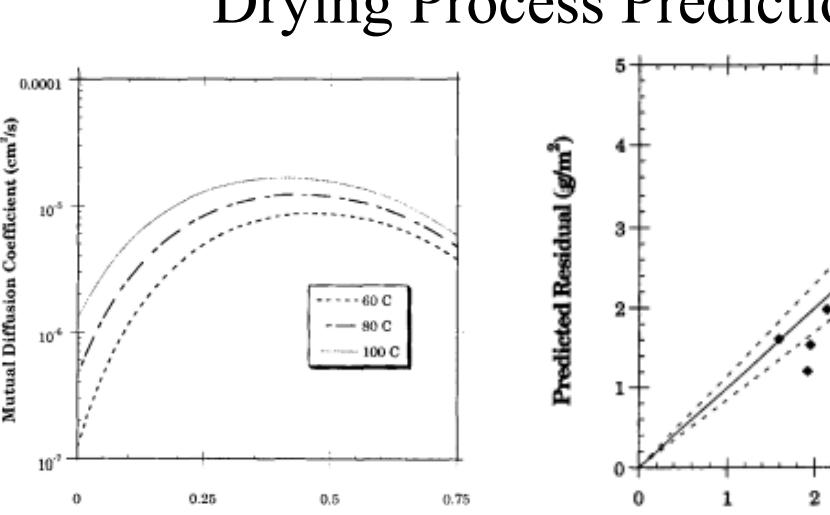
Drying Process Design: Prior Work and Challenges

Drying and Sorption Experiments



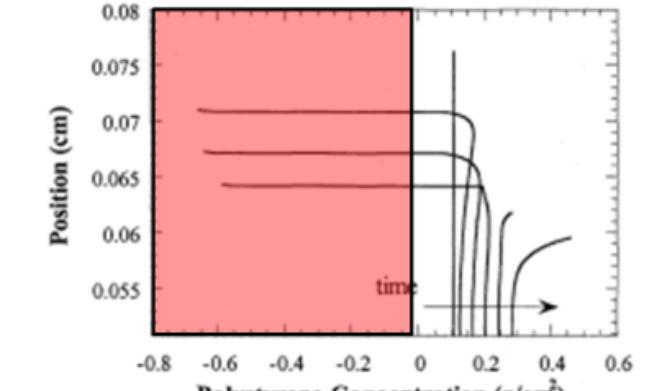
Price Jr. et al. AIChE J. 1997, 43, 1925
Schabel et al. Dry. Technol. 2004, 22, 285

Drying Process Predictions

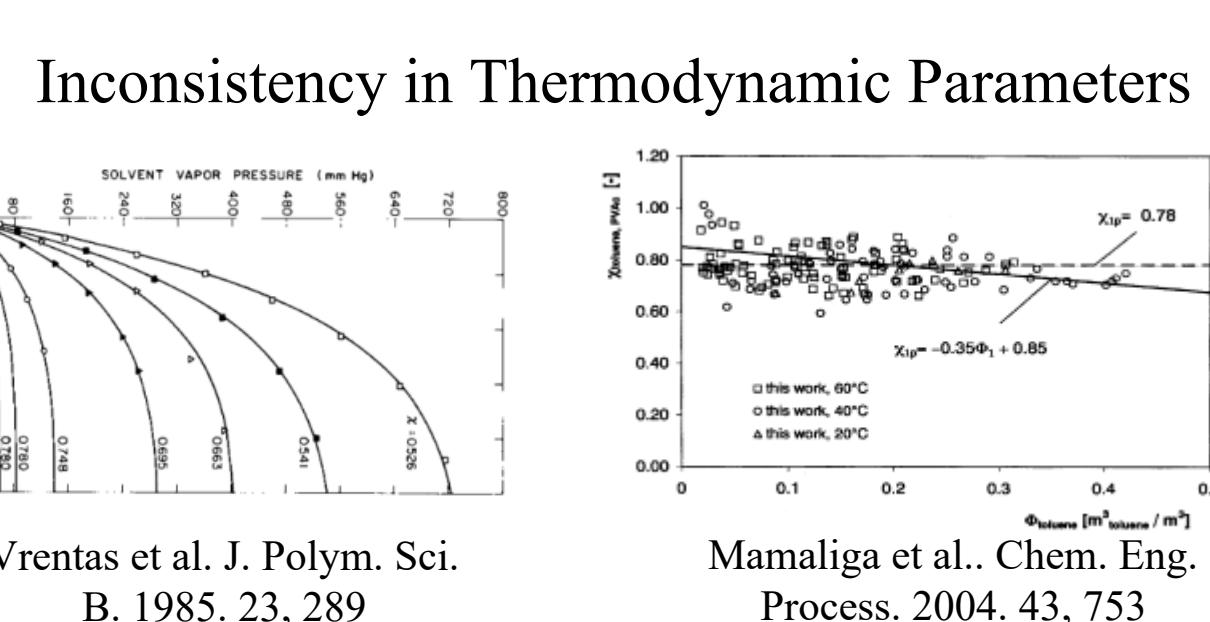


Price Jr. et al. AIChE J. 1997, 43, 1925

Ill-Posed Diffusivity Models



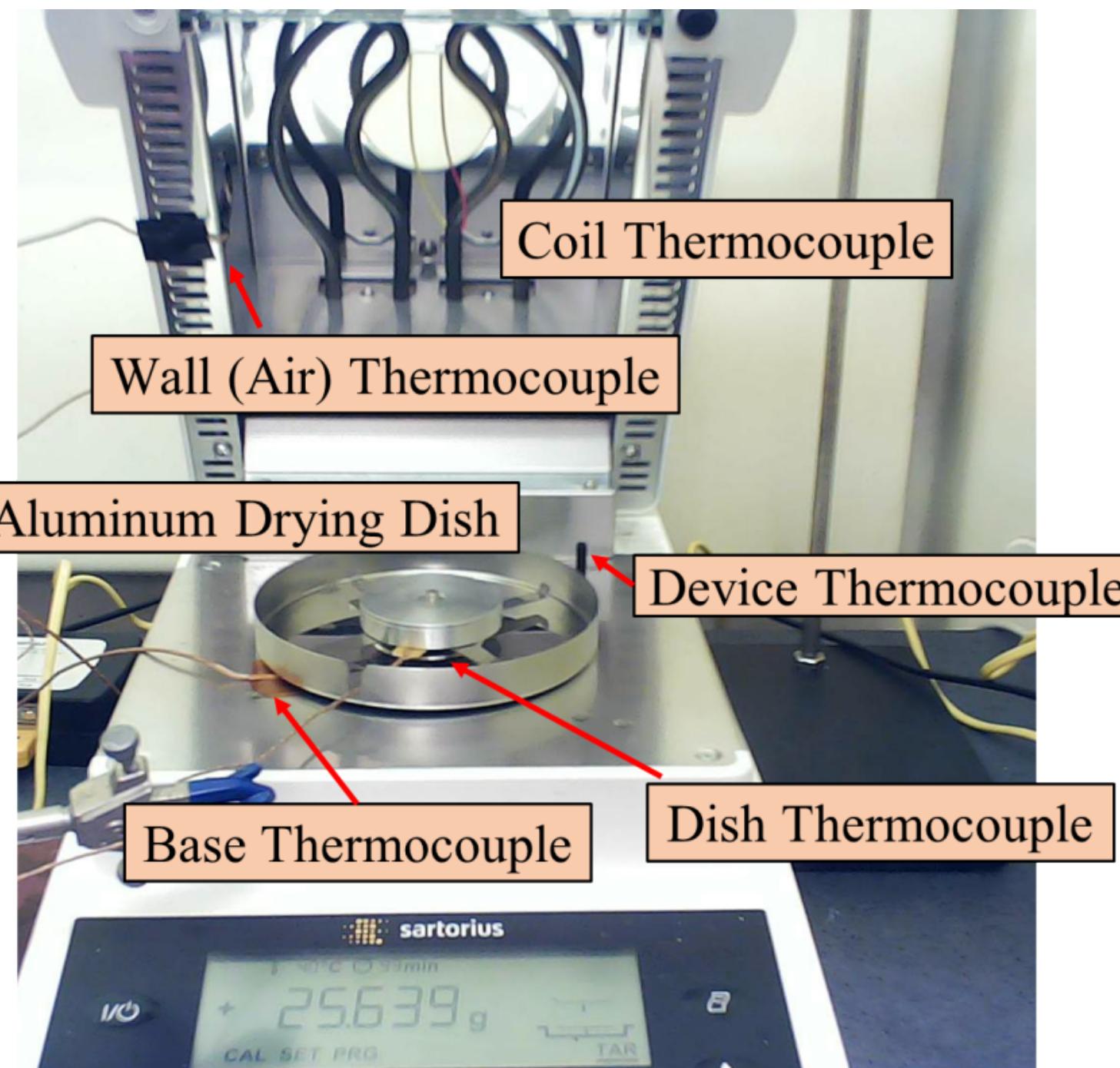
Price Jr. & Romdhane. AIChE J. 2003, 49, 309



Vrentas et al. J. Polym. Sci. B. 1985, 23, 289

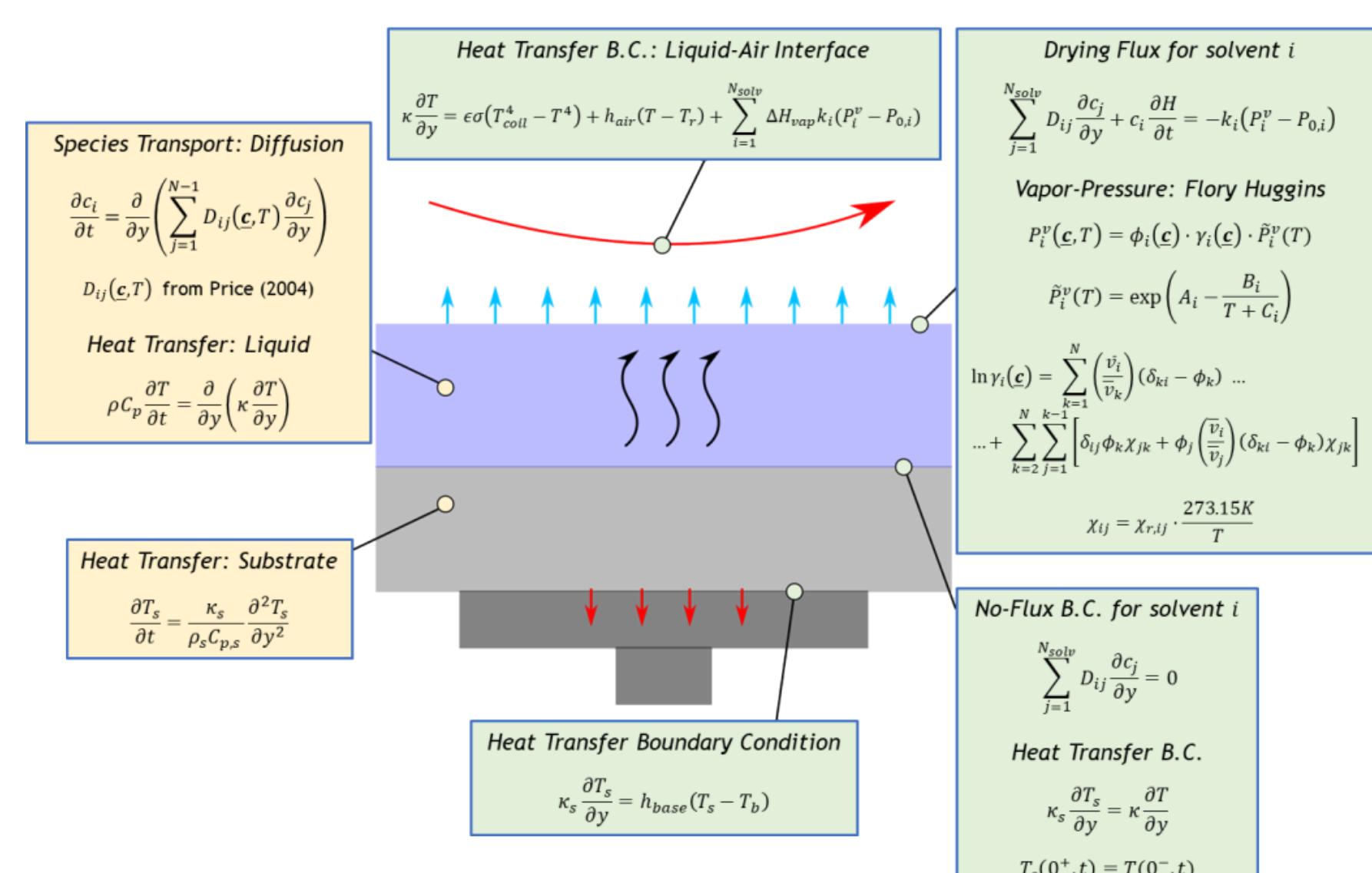
Mamaliga et al. Chem. Eng. Process. 2004, 43, 753

Benchtop Drying Apparatus



- Moisture analyzer with thermocouples and data logger provides a cost-effective drying apparatus
- Sample and surrounding temperatures may be measured and used as inputs in computational model

1D Drying Model



$$D_{ik} = D_i \left(\frac{c_i}{RT} \frac{\partial \mu_i}{\partial c_k} \right) - \sum_{j=1}^{N-1} D_j c_j \left(1 - \frac{D_N \bar{V}_N M_N}{D_j \bar{V}_j M_j} \right) \left(\frac{c_j}{RT} \frac{\partial \mu_j}{\partial c_k} \right)$$

$$D_i = D_{0,i} \exp \left(-\gamma \sum_{j=1}^N \left(\omega_j \frac{\bar{V}_j \xi_{jN}}{\bar{V}_{jH}} \right) \right) \quad \bar{V}_{jH} = \sum_{i=1}^N \frac{K_{ij}}{\gamma} \omega_i (K_{2i} - T_{gi} + T)$$

Price Jr. & Romdhane. AIChE J. 2003, 49, 309

- Key Diffusivity Parameters**
 $D_{0,i}$: infinite-dilution diffusion coefficient
 ξ_{jN} : solvent j to polymer N jumping unit ratio
 \bar{V}_j^* : critical hole volume of component i
 K_{ij}/γ : solvent free-volume params.
 $K_{2i} - T_{gi}$: polymer free-volume params.
- Key Thermodynamic Parameter**
 $\chi_{r,iN}$: FH binary interaction parameter

Free-Volume Diffusivity Model

Parameter Fitting and Single-Solvent System

Measured Residual Solvent

$$r_{i,exp} = \frac{m_{coating}(t_i) - m_{poly}}{A}$$

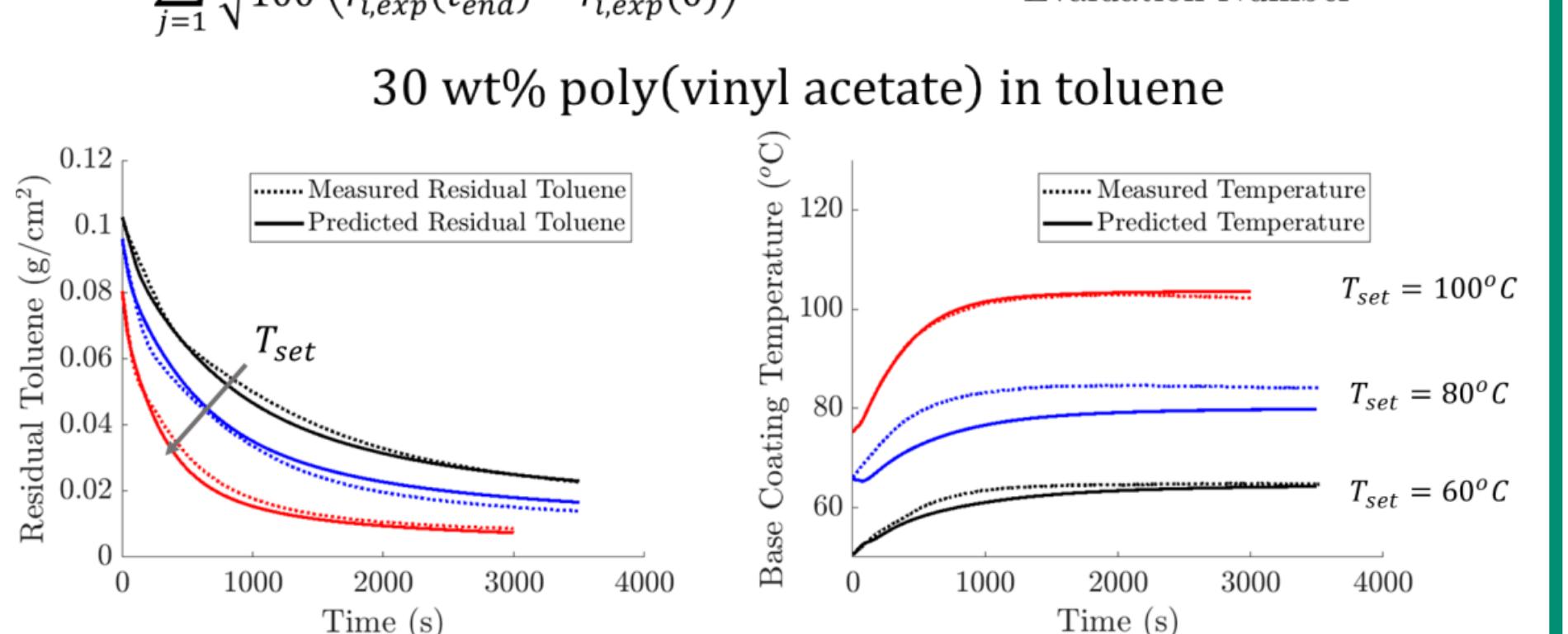
Predicted Residual Solvent

$$r_{i,pred} = \int_{x=0}^{x=h(t)} c_i(x, t_i) dx$$

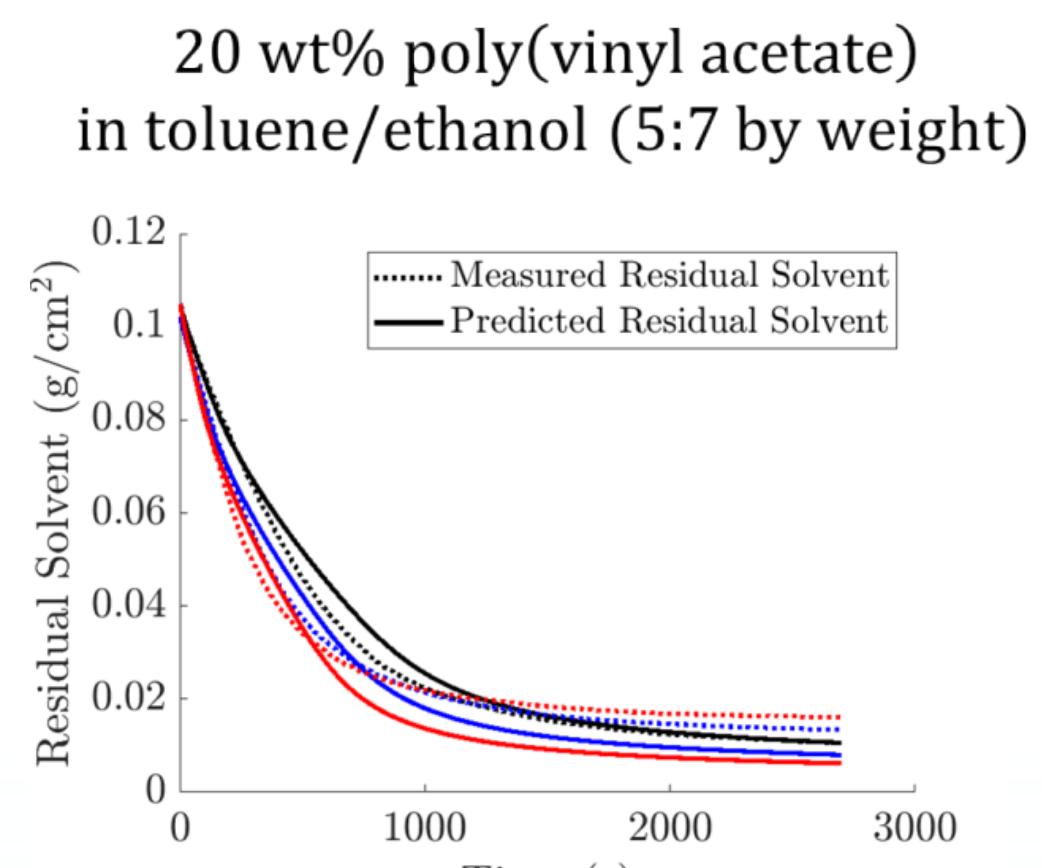
Individual Experimental Error

$$e_1^k = \sum_{j=1}^{N_{pts}} \sqrt{\frac{(1 - r_{i,pred})^2}{N_{pts}}}$$

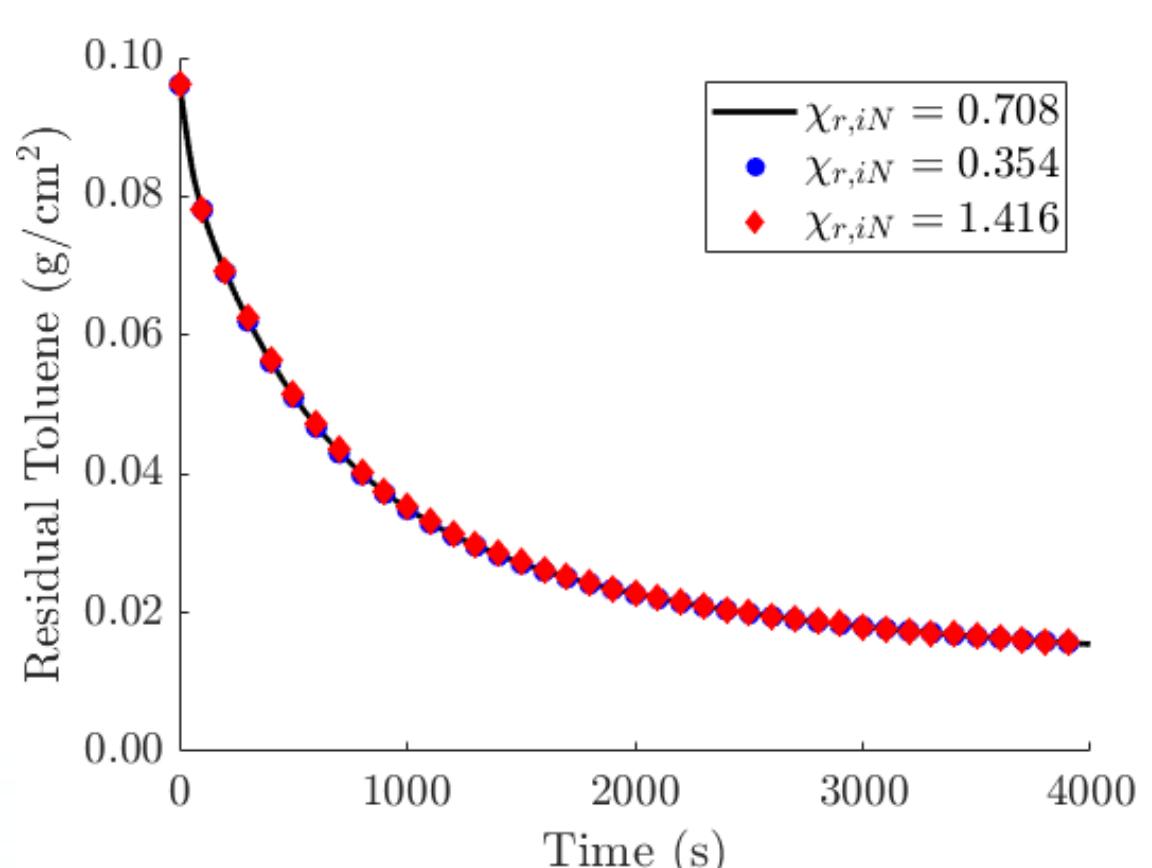
$$e_2^k = \sum_{j=1}^{N_{pts}} \sqrt{\frac{1}{100} \left(\frac{r_{i,exp} - r_{i,pred}}{r_{i,exp}(t_{end}) - r_{i,exp}(0)} \right)^2}$$



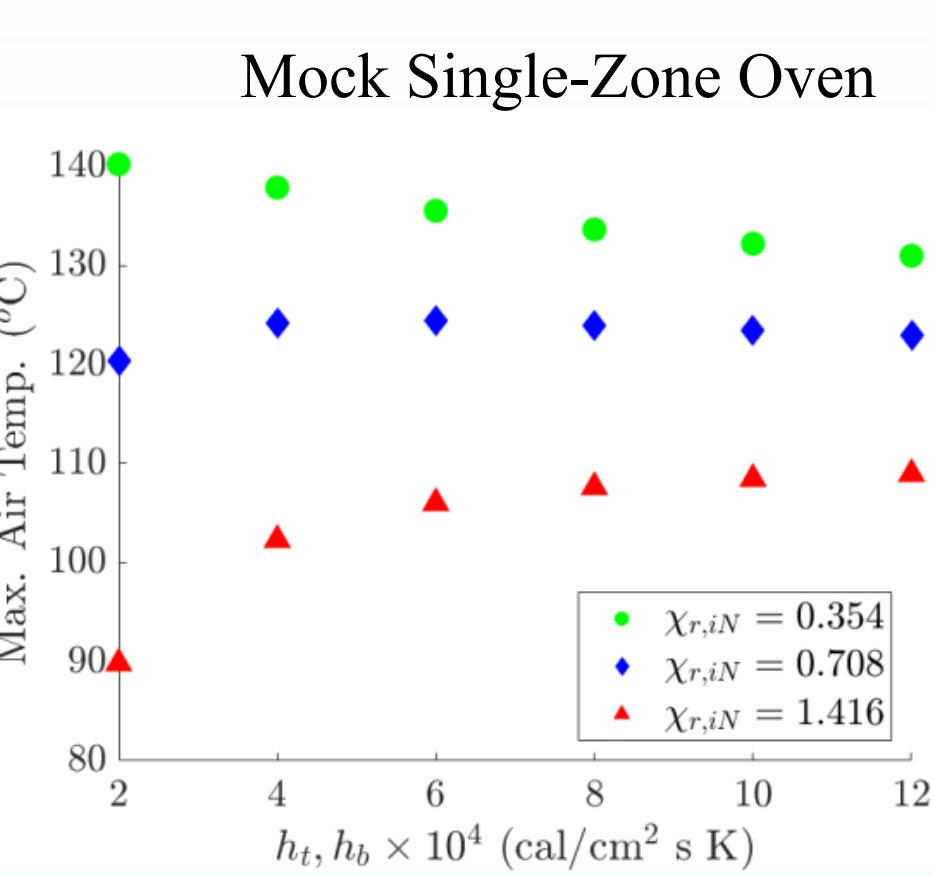
Two-Solvent System



Thermodynamic Parameters and Operating Limits

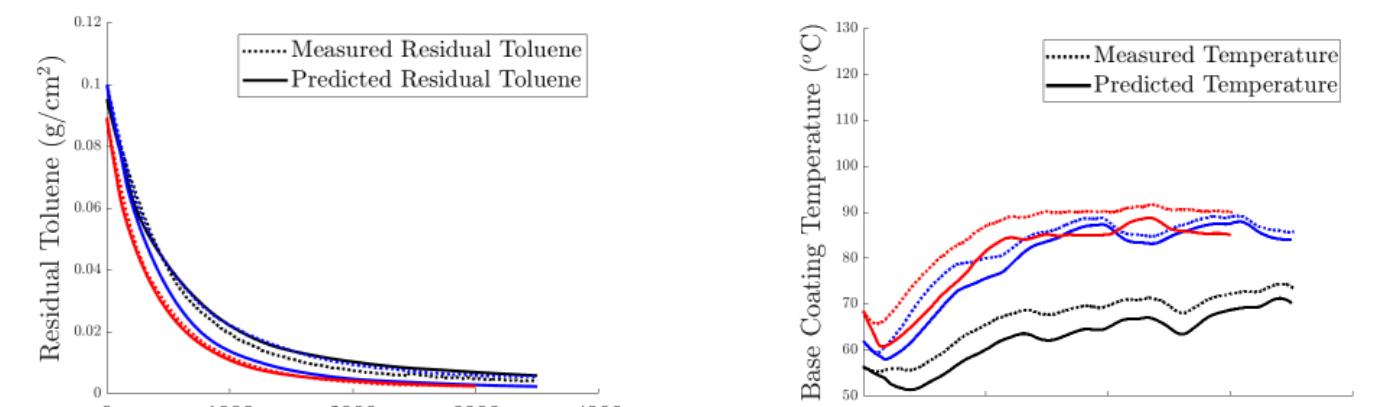


- Model predictions of residual solvent insensitive to Flory-Huggins interaction parameter
- Representative range of Flory-Huggins parameters yields large variations in vapor pressure (~ 0.1 bar)
- Variation in vapor pressure yields large spread of maximum operating temperatures for varying Flory-Huggins parameter



Conclusions

20 wt% poly(vinyl pyrrolidone) in n-propanol



- Updated models and regression are needed to account for viscoelastic effects for fast-drying coatings
- Uncertainty in Flory-Huggins Parameter hinders prediction of process operating limits

Acknowledgement

We would like to thank our collaborators within the AMO AMM R2R consortium for their useful discussions and feedback on this work. Additionally, we would like to acknowledge EERE AMO for sponsoring this work. Any opinions, findings, conclusions, or recommendations expressed in this material are those of the author(s) and do not necessarily reflect the views of the United States government or any agency thereof.

U.S. DEPARTMENT OF ENERGY | Energy Efficiency & Renewable Energy
ADVANCED MANUFACTURING OFFICE

OAK RIDGE National Laboratory
Argonne National Laboratory
INSTITUTE FOR ENERGY
RESEARCH
SANDIA National Laboratories